

Notice of References Cited

Application/Control No.

10/784,806

Applicant(s)/Patent Under

Reexamination

KIM ET AL.

Examiner

Sin J. Lee

Art Unit

1752

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-6,667,243 B1	12-2003	Ramsbey et al.	438/710
	B	US-4,732,838	03-1988	Sechi et al.	430/198
	C	US-			
	D	US-			
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	K	US-			
	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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